

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2502	(photoresist or photoresin or (photo adj (resist or resin))) near20 spray\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/26 19:42
L2	1333	1 and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/26 19:41
L4	1271	2 and (@ad<="20031030" or @rlad<="20031030")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/26 19:41
L5	5563	(photoresist or photoresin or (photo adj (resist or resin))) same harden\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/26 19:43
L6	153	4 and 5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/26 19:43